PTO/SB/08 Equivalent

	Application No.	10/781,574
INFORMATION DISCLOSURE	Filing Date	February 17, 2004
STEATEMENT BY APPLICANT	First Named Inventor	Hujanen et al.
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(Multiple sheets used when necessary)	Examiner	Kevin M. Bernatz
AIIG 0 5 2005 SHEET 1 OF 1	Attorney Docket No.	ASMMC.032DV1

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Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	
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NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹	
Plus		"ALD technology is in the process of taking off ASAP," www.micromagazine.com, 2005, 5 pages.		
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Examiner Signature	Kini	M.	Res.	Date Considered	10/14/0	5
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^{*}Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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